CONTROL DEVICE FOR SUBSTRATE TREATMENT APPARATUS, SUBSTRATE TREATMENT APPARATUS, AND DISPLAY CONTROL DEVICE

ABSTRACT OF THE DISCLOSURE

The present invention efficiently executes a plurality of functions of a substrate treatment apparatus. A control device 5 includes: a plurality of software applications (interface-related APSW 510 and control-related APSW 520) configured to execute each function of treatments concerning a CMP apparatus; and a shared memory 540 which stores information that is used in the plurality of software applications therein. The plurality of software applications include a task monitoring software application 530 which monitors whether abnormality has occurred in the plurality of software applications or not. The task monitoring software application 530 restarts the software application in which the abnormality has occurred, when the abnormality has occurred in any of the plurality of software applications, and makes the other software applications continue the respective processes.

[Selected Drawings] FIG. 5